

IN THE CLAIMS:

Please amend claims 1, 5, 19, 20 and 23 as follows:

1. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
 - carbon dioxide;
 - an additive for removing the residues comprising a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently an alkyl group, and a basic compound including a quaternary ammonium hydroxide; and
 - a co-solvent for dissolving said additive in said CO_2 at a pressurized fluid condition, wherein at least said carbon dioxide is in a supercritical state so as to maintain the composition combining said carbon dioxide, said additive and said co-solvent.
- 2-4. (Canceled).
5. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
 - carbon dioxide,
 - a compound having a hydroxyl group,
 - a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently or an alkyl group, and
 - a basic compound including a quaternary ammonium hydroxide, wherein at least said carbon dioxide is in a supercritical state so as to maintain the composition combining said carbon dioxide, said additive and said co-solvent
6. (Canceled).
7. (Original) The composition of claim 5 wherein the basic compound is selected from a mixture of the quaternary ammonium hydroxide with an alkylamine, an alkanolamine, and a hydroxylamine.

8. (Original) The composition of claim 5 further comprising a co-solvent selected from dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, and mixtures thereof.
9. (Original) The composition of claim 8 wherein the co-solvent comprises deionized water.
10. (Previously Presented) The composition of claim 8 wherein the co-solvent does not include water.
- 11-12. (Canceled).
13. (Currently Amended) The composition of claim 5 wherein the fluoride is selected from tetramethylammoniumfluoride, tetraethylammonium-fluoride, tetrabutylammoniumfluoride, tetrapropylammoniumfluoride, choline fluoride, and mixtures thereof.
14. (Original) The composition of claim 5 wherein the compound is selected from ethanol, methanol, n-propanol, isopropanol, n-butanol, iso-butanol, diethyleneglycolmonomethylether, diethyleneglycolmonoethylether, hexafluoroisopropanol, and mixtures thereof.
15. (Canceled)
16. (Previously Presented) The composition of claim 19 wherein the additive is dissolved within the co-solvent.
17. (Canceled)
18. (Previously Presented) The composition of claim 19 wherein the residues are at least one selected from photoresist, UV-hardened resist, X-ray hardened resist, ashed resists, carbon-fluorine containing polymer, plasma etch residues, organic process contaminants, and inorganic process contaminants.

19. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
- carbon dioxide wherein the carbon dioxide is in a pressurized or a supercritical fluid state;
 - an additive comprising a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently an alkyl group, and mixtures thereof and a basic compound including a quaternary ammonium hydroxide; and
 - a co-solvent selected from an alcohol, dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, acetone, ethanol, propanol, dimethylformamide, N-methyl-2-pyrrolidone, diethylene glycol methyl ether, and mixtures thereof, wherein at least said carbon dioxide is in a supercritical state so as to maintain the composition combining said carbon dioxide, said additive and said co-solvent.
20. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
- from 0.001 to 8 weight percent of an additive comprising a fluoride having a formula $NR_1R_2R_3R_4F$, where R_1 , R_2 , R_3 , and R_4 are each independently an alkyl group, and mixtures thereof and a basic compound including a quaternary ammonium hydroxide;
 - from 1 to 50 weight percent of a co-solvent selected from an alcohol, dimethylacetamide, propylene glycol, dimethylsulfoxide, deionized water, acetic acid, acetone, ethanol, propanol, dimethylformamide, N-methyl-2-pyrrolidone, diethylene glycol methyl ether, and mixtures thereof; and
 - carbon dioxide, wherein at least said carbon dioxide is in a supercritical state so as to maintain the composition combining said carbon dioxide, said additive and said co-solvent.
21. (Previously Presented) The composition of claim 20 wherein the additive further comprises methane.

22. (Previously Presented) The composition of claim 20 wherein the additive further comprises a surfactant having a CF_x group.
23. (Currently Amended) A composition for removing residues from the microstructure of an object comprising:
- carbon dioxide;
 - an additive for removing the residues comprising a fluoride having a formula NR₁R₂R₃R₄F, where R₁, R₂, R₃, and R₄ are each independently a hydrogen or an alkyl group, and a quaternary ammonium hydroxide; and
 - a co-solvent for dissolving said additive in said CO₂ at a pressurized fluid condition, wherein at least said carbon dioxide is in a supercritical state so as to maintain the composition combining said carbon dioxide, said additive and said co-solvent.